

	Hits	Search Text	DBs
7	14	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same cur\$4) and ((resist or photoimageable or photoresist) same (liquid or ink) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
8	15	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4) same develop\$4 same cur\$4) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	16	((resist or photoresist or photoimageable) same laminat\$4 same (substrate or wafer or carrier or release) same (expos\$4 or irradiat\$4 or illuminat\$4)) and ((resist or photoimageable or photoresist) same (liquid or ink or fluid) same (film or coat\$4 or deposit\$4 or form\$3 or layer) same (dry\$4 or heat\$4 or bak\$4 or dried) same (carrier or sheet or transfer or (temporary near5 sheet)) same transparent same laminat\$4) and develop\$5 and cur\$3	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB